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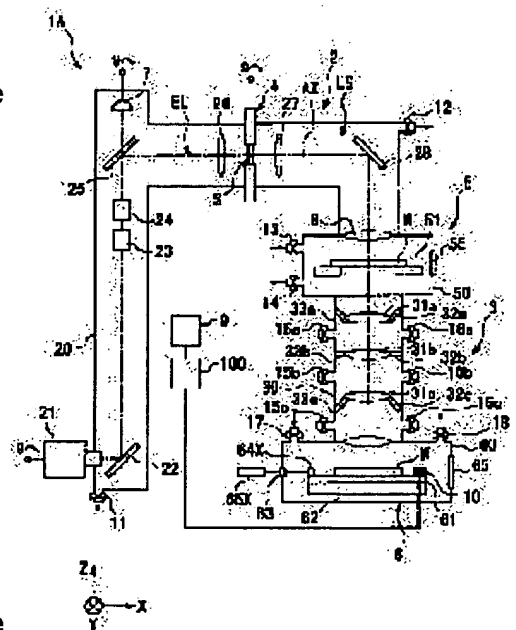
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## (54) LIGHT ABSORBING SUBSTANCE DETECTING METHOD, AND EXPOSURE METHOD AND APPARATUS

(57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a light absorbing substance detecting method, and an exposure method and apparatus which can detect a concentration or the like of a light absorbing substance in a short time with a good efficiency and accuracy.

**SOLUTION:** An exposure apparatus 1A includes an instrument 10 for measuring information about an intensity of exposure light EL passing through an optical space LS, a calculator 100 connected to the measuring device 10, and a controller 9 for controlling the exposure apparatus 1A on the basis of a calculated result of the calculator 100. The calculator 100 calculates a concentration of a light absorbing substance in the space LS on the basis of a calculated result of the measuring device 10, and the controller 9 judges whether or not to transfer an image of a pattern of a mask M onto a substrate W according to the concentration.



## LEGAL STATUS

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